

Mentor Graphics Calibre

Mentor Graphics Calibre is one of the most popular tools that is widely used by design organizations and foundries. Calibre has different modules that perform a variety of functions post-tapeout. The challenge of the post-tapeout workflow is maintaining tight control for high wafer yield that would lead to a reduction in the time-to-mask and operation costs. This process handles different parts of the workflow from Calma Graphic Data System (GDSII) to mask flow, providing high wafer yield and reducing the cost of operation.

Key Features:

- The input files provided include physical details of SoCs in a GDSII or OASIS format
- Getting more optimized to reduce the time to mask
- The underlying storage infrastructure also plays a significant role on turn around time (TAT)
- The infrastructure consists of network file share storage, the network layer, and the compute farm
- NetApp storage is primarily used to store the GDSII/OASIS files
- The chip design goes from conceptualizing a logical design to physically - manufacturing it on a silicon chip
- And more